

AMENDMENTS TO THE SPECIFICATION:

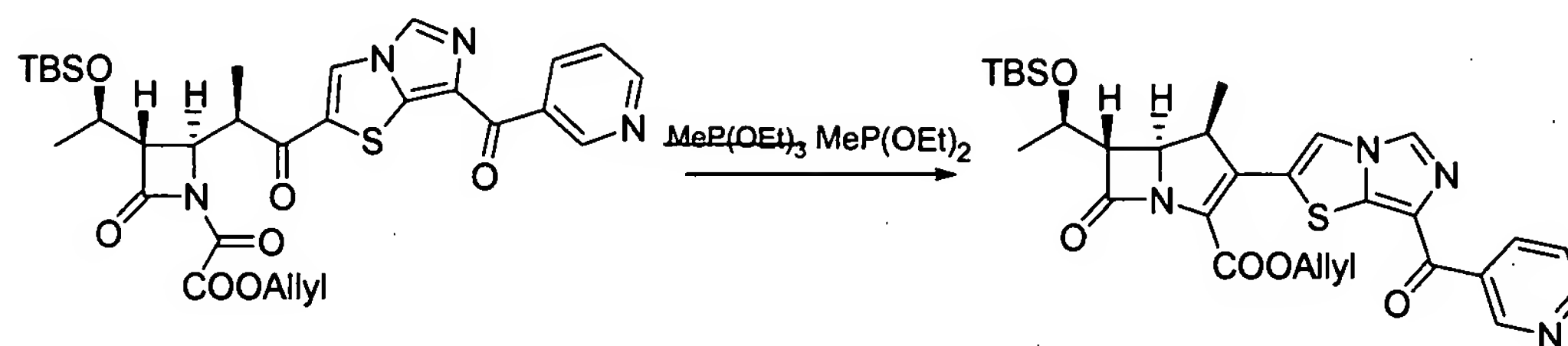
Page 1, after the title, please insert the following new paragraph:

This application is a national stage of PCT/JP2003/016036, filed December 15, 2003, which claims priority to Japanese Patent Application No. 2002-361757, filed December 13, 2002, the entireties of which are hereby incorporated by reference.

Page 63, 1st paragraph, lines 4-25, please amend to read as follows:

The compound of formula (A) can be produced by removing the protective group of the compound of formula (3) by deprotection. The reaction for removing the protective group of hydroxyl and the protective group of carboxyl may vary depending upon the type of the protective group. The reaction, however, may be carried out by using as reference a reaction for removing a protective group of hydroxyl in the conventional organic synthetic chemistry. For example, when the protective group R¹ of hydroxyl is triethylsilyl, triethylsilyl as the protective group can be removed by reacting the compound of formula (3) with an acid such as hydrochloric acid, sulfuric acid, methanesulfonic acid, or trifluoroacetic acid, or a fluorine reagent such as tetrabutylammonium fluoride, in an amount of 0.1 to 10 molar equivalents relative to the compound of formula (3) in a solvent inert to the reaction, for example, methanol, ethanol, water, tetrahydrofuran, dioxane, dimethylformamide, methylene chloride, chloroform, acetone, or acetonitrile, at a temperature in a range of -20°C to the reflux temperature of the solvent used for 10 min to 24 hr. When the protective group R of carboxyl is 4-nitrobenzyl (pNB), the protective group can be removed by the method described in ~~WO 02/42314~~ WO 02/42312.

Page 84, the reaction step at lines 3-4, please amend to read as follows:



Page 85, the reaction step at line 28, please amend to read as follows:

